

AMENDMENTS TO THE CLAIMS

The following listing of claims will replace all prior versions and listings of claims in the application.

LISTING OF CLAIMS

1. (previously amended) A liquid crystal device comprising:

a first substrate;

a second substrate disposed so as to oppose the first substrate;

a color layer provided on the first substrate;

an insulating film provided on the color layer and comprising at least one of Ta₂O₅, ZrO₂, and TiO₂ as a primary component; and

a conductive film having a property of transmitting light provided on the insulating film.

2. (previously amended) A liquid crystal device according to Claim 1, wherein, when an optional wavelength in a visible wavelength region is represented by λ , a sum of an optical thickness of the insulating film and an optical thickness of the conductive film is substantially equal to a product of $\lambda/2$ and a natural number.

3. (previously amended) A liquid crystal device according to Claim 2, wherein λ is 550 nm.

4. (previously amended) A liquid crystal device according to Claim 1, further comprising a transparent resin film between the color layer and the insulating film.

5. (previously amended) A liquid crystal device according to Claim 1, further comprising a reflective film between the color layer and the first substrate.

6. (previously amended) A liquid crystal device according to Claim 1, further comprising an underlying layer provided on the second substrate and composed of a material substantially identical to that for the insulating film, and an active element provided on the underlying layer.

7. (previously amended) A liquid crystal device according to Claim 5, wherein the reflective layer has an opening portion therein.

8. (previously amended) A liquid crystal device according to Claim 6, wherein the active element is a TFD.

9. (previously amended) A liquid crystal device comprising:

- a first substrate;
- a second substrate disposed so as to oppose the first substrate;
- a color layer provided on the first substrate;
- an insulating film provided on the color layer and comprising Ta_2O_5 as a primary component; and
- a conductive film having a property of transmitting light provided on the insulating film.

10. (previously amended) A liquid crystal device according to Claim 9, wherein the insulating film further comprises at least one of ZrO_2 , TiO_2 , and SiO_2 as a component.

11. (previously amended) A liquid crystal device according to Claim 10, wherein, when an optional wavelength in a visible wavelength region is represented by λ , a sum of an optical thickness of the insulating film and an optical thickness of the conductive film is substantially equal to a product of $\lambda/2$ and a natural number.

12. (previously amended) A liquid crystal device according to Claim 11, wherein λ is 550 nm.

13. (previously amended) A liquid crystal device according to Claim 9, further comprising a transparent resin film provided between the color layer and the insulating film.

14. (previously amended) A liquid crystal device according to Claim 9, further comprising a reflective film provided between the color layer and the first substrate.

15. (previously amended) A liquid crystal device according to Claim 9, further comprising an underlying layer provided on the second substrate and composed of a

material substantially identical to that for the insulating film, and an active element provided on the underlying layer.

16. (previously amended) A liquid crystal device according to Claim 14, wherein the reflective layer has an opening portion therein.

17. (previously amended) A liquid crystal device according to Claim 15, wherein the active element is a TFD.

18. (previously amended) A liquid crystal device comprising:
an insulating film comprising at least one of Ta₂O₅, ZrO₂, and TiO₂ as a primary component; and
a conductive film having a property of transmitting light provided on the insulating film.

19. (previously amended) A liquid crystal device according to Claim 18, wherein, when an optional wavelength in a visible wavelength region is represented by λ , a sum of an optical thickness of the insulating film and an optical thickness of the conductive film is substantially equal to a product of $\lambda/2$ and a natural number.

20. (previously amended) A liquid crystal device according to Claim 19, wherein λ is 550 nm.

21. (previously amended) A liquid crystal device comprising:

- a first substrate;
- a second substrate disposed so as to oppose the first substrate;
- a color layer provided on the first substrate;
- an insulating film provided on the color layer, having a property of transmitting light, a refractive index of 1.6 to 2.0 in a visible wavelength region, and a thickness of 10 nm to 100 nm; and
- a conductive film provided on the insulating film, having the property of transmitting light, a refractive index of 1.8 to 1.9 in the visible wavelength region, and a thickness of 100 nm to 300 nm.

22. (previously amended) A liquid crystal device according to Claim 21, wherein, when an optional wavelength in the visible wavelength region is represented by λ , a sum of an optical thickness of the insulating film and an optical thickness of the conductive film is substantially equal to a product of $\lambda/2$ and a natural number.

23. (Currently amended) A liquid crystal device according to Claim 1 wherein comprising:

- ~~an~~ the insulating film ~~having~~ has a refractive index of 1.6 to 2.0 in a visible wavelength region and a thickness of 10 nm to 100 nm; and

- ~~a~~ the conductive film ~~provided on the insulating film, having~~ has a property of transmitting light, a refractive index of 1.8 to 1.9 in the visible wavelength region, and a thickness of 100 nm to 300 nm.

24. (previously amended) A liquid crystal device according to Claim 23, wherein, when an optional wavelength in the visible wavelength region is represented by λ , a sum of an optical thickness of the insulating film and an optical thickness of the conductive film is substantially equal to a product of $\lambda/2$ and a natural number.

25. (previously amended) A color filter substrate comprising:
a substrate;
a color layer provided on the substrate;
an insulating film provided on the color layer and comprising one of Ta_2O_5 , ZrO_2 , and TiO_2 as a primary component; and
a conductive film having a property of transmitting light provided on the insulating film.

26. (previously amended) A color filter substrate according to Claim 25, wherein, when an optional wavelength in a visible wavelength region is represented by λ , a sum of an optical thickness of the insulating film and an optical thickness of the conductive film is substantially equal to a product of $\lambda/2$ and a natural number.

27. (previously amended) A color filter substrate according to Claim 26, wherein λ is 550 nm.

28. (previously amended) A color filter substrate according to Claim 25, further comprising a transparent resin film provided between the color layer and the insulating film.

29. (previously amended) A color filter substrate according to Claim 25, further comprising a reflective film provided between the color layer and the first substrate.

30. (previously amended) A color filter substrate according to Claim 29, wherein the reflective layer has an opening portion therein.

31. (previously amended) A color filter substrate comprising:
a substrate;
a color layer provided on the substrate;
an insulating film provided on the color layer and comprising Ta_2O_5 as a primary component; and
a conductive film having a property of transmitting light provided on the insulating film.

32. (previously amended) A color filter substrate according to Claim 31, wherein the insulating film further comprises at least one of ZrO_2 , TiO_2 , and SiO_2 as a component.

33. (previously amended) A color filter substrate according to Claim 32, wherein, when an optional wavelength in a visible wavelength region is represented by λ , a sum of an optical thickness of the insulating film and an optical thickness of the conductive film is substantially equal to a product of $\lambda/2$ and a natural number.

34. (previously amended) A color filter substrate according to Claim 33, wherein λ is 550 nm.

35. (previously amended) A color filter substrate according to Claim 31, further comprising a transparent resin film provided between the color layer and the insulating film.

36. (previously amended) A color filter substrate according to Claim 31, further comprising a reflective film provided between the color layer and the first substrate.

37. (previously amended) A liquid crystal device according to Claim 36, wherein the reflective layer has an opening portion therein.

38. (previously amended) A color filter substrate comprising:
a substrate;
a color layer provided on the substrate;

an insulating film provided on the color layer, having a property of transmitting light, a refractive index of 1.6 to 2.0 in a visible wavelength region, and a thickness of 10 nm to 100 nm; and

a conductive film provided on the insulating film, having the property of transmitting light, a refractive index of 1.8 to 1.9, and a thickness of 100 nm to 300 nm.

39. (previously amended) A color filter substrate according to Claim 38, wherein, when an optional wavelength in the visible wavelength region is represented by λ , a sum of an optical thickness of the insulating film and an optical thickness of the conductive film is substantially equal to a product of $\lambda/2$ and a natural number.

40. (previously amended) A method for manufacturing a liquid crystal device, comprising:

a step of forming a color layer on a first substrate;

a step of forming an insulating film on the color layer, the insulating film comprising at least one of Ta_2O_5 , ZrO_2 , and TiO_2 as a primary component;

a step of forming a conductive film having a property of transmitting light on the insulating film; and

a step of patterning the conductive film by using an alkaline solution.

41. (previously amended) A method for manufacturing a liquid crystal device, according to Claim 40, wherein the insulating film and the conductive film are formed so that when an optional wavelength in a visible wavelength region is represented by λ , a

sum of an optical thickness of the insulating film and an optical thickness of the conductive film is substantially equal to a product of $\lambda/2$ and a natural number.

42. (previously amended) A method for manufacturing a liquid crystal device, according to Claim 40, further comprising a step of forming a transparent resin film on the color layer.

43. (previously amended) A method for manufacturing a liquid crystal device, according to Claim 40, further comprising a step of forming a reflective film on the first substrate.

44. (previously amended) A method for manufacturing a liquid crystal device, according to Claim 40, further comprising: a step of forming an underlying layer on a second substrate, the underlying layer comprising a material substantially identical to that for the insulating film; and a step of forming an active element on the underlying layer.

45. (previously amended) A method for manufacturing a liquid crystal device, according to Claim 43, further comprising a step of forming an opening portion in the reflective film.

46. (previously amended) A method for manufacturing a liquid crystal device, according to Claim 40, wherein the insulating film is formed by vapor phase film-forming means.

47. (previously amended) A method for manufacturing a liquid crystal device, comprising:

a step of forming a color layer on a substrate;

a step of forming an insulating film on the color layer, the insulating film comprising Ta_2O_5 as a primary component and at least one of ZrO_2 , TiO_2 , and SiO_2 as a component;

a step of forming a conductive film having a property of transmitting light on the insulating film; and

a step of patterning the conductive film by using an alkaline solution.

48. (previously amended) A method for manufacturing a liquid crystal device, comprising:

a step of forming a color layer on a substrate;

a step of forming an insulating film on the color layer, the insulating film having a property of transmitting light, a refractive index of 1.6 to 2.0 in a visible wavelength region, and a thickness of 10 nm to 100 nm; and

a step of forming a conductive film on the insulating film, the conductive film having the property of transmitting light, a refractive index of 1.8 to 1.9 in the visible wavelength region, and a thickness of 100 nm to 300 nm.

49. (previously amended) A method for manufacturing a color filter substrate, comprising:

- a step of forming a color layer on a substrate;
- a step of forming an insulating film on the color layer, the insulating film comprising at least one of Ta₂O₅, ZrO₂, and TiO₂ as a primary component;
- a step of forming a conductive film having a property of transmitting light on the insulating film; and
- a step of patterning the conductive film by using an alkaline solution.

50. (previously amended) A method for manufacturing a color filter substrate according to Claim 49, wherein the insulating film and the conductive film are formed so that when an optional wavelength in a visible wavelength region is represented by λ , a sum of an optical thickness of the insulating film and the optical thickness of the conductive film is substantially equal to a product of $\lambda/2$ and a natural number.

51. (previously amended) A method for manufacturing a color filter substrate according to Claim 49, further comprising a step of forming a transparent resin film on the color layer.

52. (previously amended) A method for manufacturing a color filter substrate according to Claim 49, further comprising a step of forming a reflective film on the substrate.

53. (previously amended) A method for manufacturing a color filter substrate according to Claim 52, further comprising a step of forming an opening portion in the reflective film.

54. (previously amended) A method for manufacturing a color filter substrate according to Claim 49, wherein the insulating film is formed by vapor phase film-forming means.

55. (previously amended) A method for manufacturing a color filter substrate, comprising:

a step of forming a color layer on a substrate;

a step of forming an insulating film on the color layer, the insulating film having a property of transmitting light, a refractive index of 1.6 to 2.0 in a visible wavelength region, and a thickness of 10 nm to 100 nm; and

a step of forming a conductive film on the insulating film; the conductive film having the property of transmitting light, a refractive index of 1.8 to 1.9 in the visible wavelength region, and a thickness of 100 nm to 300 nm.